



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of

Masahiro Yoshida et al.

Group Art Unit: 2818

Serial No.: 09/759,639

Examiner: T. Ho

Filed: January 16, 2001

For: SEMICONDUCTOR DEVICE HAVING A THICK OXIDE LAYER UNDER GATE
SIDE WALLS AND METHOD FOR MANUFACTURING THE SAME (As
Amended)

RESPONSE TO RESTRICTION REQUIREMENT

Honorable Assistant Commissioner for Patents
Washington, D.C. 20231

Date: July 31, 2002

Sir:

In response to the Office Action dated July 5, 2002, the following election and
remarks are respectfully submitted in connection with the above-identified application.

In the Claims:

Applicants respectfully elect the Group I invention including claims 1-14 for
further prosecution on the merits on the present application. This election is with
traverse.

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Election
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